

Korean International Semiconductor Conference & Exhibition on Manufacturing Technology 2025

KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[WeD2]	Material & Process
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Session Date November 12 (Wed.), 2025

Session Time 14:10-15:50

Session Room D (Sidney Room, 2F)

[WeD2-1] [Invited] 14:10-14:40

Advanced Patterning: Tackling the Big Problems in Printing Small Features

Ben Eynon (Lam Research, USA)

[WeD2-2] [Invited] 14:40-15:10

Understanding of Novel Patterning Materials Approacing to Next Gen Lithography

Ethan C B Lee (SDI, Korea)

[WeD2-3] [Invited] 15:10-15:30

EUV vs. E-Beam Photoresists: Cross-Platform Analysis and Optimization Strategies

Hyungkun Lee, Jaehyun Kim, Myounghyun Hur, Jeongwoo Kim, and Jeongsik Kim (Dongjin Semichem Co., Ltd., Korea)

[WeD2-4] [Invited] 15:30-15:50

EUV Mask Local CD Correction System Development via Laser Irradiation

Hyun Yoon, Yujin Cho, Ki Hoon Choi, Hojong Hwang, Seung Eon Oh, Seryeyohan Cho, Jin Yeong Sung, Jangjin Lee, Taeshin Kim, Sang Hyeon Ryu, Youngho Park, Donggeun Lee, Joon Ho Won (SEMES, Korea), Yong Woo Kim, Jong Keun Oh, Jong Ju Park (Samsung Electronics Co., Ltd., Korea), and Byeonggeun Kim (SEMES, Korea)